	Hits	Search Text	DBs
4	0	((CPP or GMR or (giant near9 magneto\$4resist\$6)) same transducer same (spin near12 valve)) and (seed near9 layer) and (cap\$4) and (anti\$4ferro\$5magnet\$4) and ((ferro\$4magnetic or NiFe or FeMn) near16 layer) and (spacer or ((dead or Cu or copper) near9 layer)) and (pinn\$4 near12 layer) and (substrate or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
5			USPAT; EPO; JPO; DERWENT;
6	11	(anti\$4ferro\$5magnet\$4) and ((ferro\$4magnetic or NiFe or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
7	0	((CPP or GMR or (giant near9 magneto\$4resist\$6)) same transducer same (spin near12 valve)) and (anti\$4ferro\$5magnet\$4) and ((ferro\$4magnetic or NiFe or FeMn) near16 layer) and (spacer or ((dead or Cu or copper) near9 layer)) and (substrate or wafer or sheet) and ((resist or photoresist or alumina) same (mask or pattern or photolithograph\$4) same (undercut\$4 or shadow\$4) same (etch\$4 or (ion near9 beam near6 etch\$4) or IBE or IABE))	USPAT; EPO; JPO; DERWENT;
8	O .	(spacer or ((dead or Cu or copper) near9 layer)) and	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
9	0	or FeMn) near16 layer) and (substrate or wafer or sheet) and ((resist or photoresist or alumina) same (mask or pattern or photolithograph\$4) same (undercut\$4 or shadow\$4) same (etch\$4 or (ion near9 beam near6 etch\$4) or IBE or IABE))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	2	or sneet) and ((resist or photoresist or alumina) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
11	8	((CPP or GMR or (giant near12 magneto\$4resist\$6)) same transducer) and (substrate or wafer or sheet) and ((resist or photoresist or alumina) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
12	37	((CPP or GMR or (giant near12 magneto\$4resist\$6) or (magnetic near9 head)) same transducer) and (substrate or wafer or sheet) and ((resist or photoresist or alumina) same (mask or pattern or photolithograph\$4) same (undercut\$4 or shadow\$4) same (etch\$4 or (ion near9 beam near22 etch\$4) or IBE or IABE))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
13	42	((CPP or GMR or (giant near12 magneto\$4resist\$6) or (magnetic near9 head)) same transducer) and (substrate or wafer or sheet) and ((resist or photoresist or alumina) same	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	0	((CPP or GMR or (giant near12 magneto\$4resist\$6) or (magnetic near9 head)) same transduc) and (substrate or wafer or sheet) and ((resist or photoresist or alumina) same (mask or pattern	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
15	108	((CPP or GMR or (giant near12 magneto\$4resist\$6) or (magnetic near9 head)) same transduc\$4) and (substrate or wafer or sheet) and ((resist or photoresist or alumina) same (mask or pattern or photolithograph\$4) same (undercut\$4 or shadow\$4) same ((ion\$4 near16 mill\$4) or etch\$4 or (ion near9 beam near22 etch\$4) or IBE or IABE))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
16	8	(mask or pattern or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

, [Hits	Search Text	DBs
	17	64	((CPP or GMR or (giant near12 magneto\$4resist\$6) or (magnetic near9 head)) same transduc\$4) and (substrate or wafer or sheet) and ((resist or photoresist or alumina) same (mask or pattern or photolithograph\$4) same (undercut\$4 or shadow\$4) same ((ion\$4 near16 mill\$4) or etch\$4 or (ion near9 beam near22 etch\$4) or IBE or IABE)) and (overhang or overetch\$4 or ((rotat\$4 or mov\$3 or tilt\$4) same (substrate or wafer or GMR or (ion near9 source))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
	L8	0	((CPP or GMR or (giant near12 magneto\$4resist\$6) or (magnetic near9 head)) same transduc\$4) and (substrate or wafer or sheet) and ((resist or photoresist or alumina) same (mask or pattern or photolithograph\$4) same (undercut\$4 or shadow\$4)) and (((ion\$4 near16 mill\$4) or etch\$4 or (ion near9 beam	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
19	3	l((lons4 nearl6 mills4) or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
20	3	((CPP or GMR or (giant near12 magneto\$4resist\$6) or (magnetic near9 head)) same transduc\$4) and (substrate or wafer or sheet) and (mask or pattern or photolithograph\$4) and ((ion\$4 near16 mill\$4) or etch\$4 or (ion near9 beam near22 etch\$4) or IBE or IABE) same (rotat\$4 or spin\$4) same (tilt\$4 or slop\$4 or undercut\$4 or overhang) same angle same (vary4 or different or adjust)) and (overhang or overetch\$4 or ((rotat\$4 or mov\$3 or tilt\$4) same (substrate or wafer or GMR or (ion near9 source))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
21	12	llion neary beam nearly etchs4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
22	0	(CPP or GMR or (giant near12 magneto\$4resist\$6) or (magnetic near9 head) or stack) and (substrate or wafer or sheet) and (mask or pattern or photolithograph\$4) and (((ion\$4 near16 mill\$4) or etch\$4 or (ion near9 beam near22 etch\$4) or IBE or IABE) same (rotat\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
23	6	(("20050058952") or ("20050106509") or ("6759084")	US-PGPUB; USPAT

	Hits	Search Text	DBs
24	0	HARE) game (rotats4 or gnins4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
25	4	near6 angle) or (chang\$4 near8 angle) or (different near9	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
26	1	("5420880").PN.	US-PGPUB; USPAT

	Hits	Search Text	DBs
27	24	angle) or (chang\$4 hear8 angle) or (different hear9 angle))) and ((ion hear6 beam	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
28	0	(angle or tilt\$4 or rotat\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
29	51	(mask or pattern or photolithograph\$4 or ((resist or photoresist) near12 (mask or structure or pattern))) and (((ion near9 mill\$4) or (ion near9 beam) or IBE or (ion near6 beam near9 source) or (ion near9 source) or (ion near9 (gun or module))) same (angle or tilt\$4 or rotat\$4 or	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits			Search	Text	DBs
30	48	S29. NC	мот	r S27		 US-PGPUB;
						USPAT; EPO;
			MOI			JPO; DERWENT;
].				•	IBM TDB